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09/788,365INFORMATION DISCLOSURE  
STATEMENT BY APPLICANT

APPLICANT

Tuqiang NI et al.

FILING DATE  
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PATENT &amp; TRADEMARK OFFICE

## U.S. PATENT DOCUMENTS

Examiner Initials	Patent Document		Name of Patentee or Applicant of Cited Document	C.	S.C.	Date of Publication (MM-DD-YYYY)
	Number	Kind Code (if known)				
RZ	4,270,999		Hassan et al.	156	34533	06/02/81
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	4,992,301		Shishiguchi et al.	118	730	02/12/91
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	5,134,965		Tokuda et al.	118	715	08/04/92
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## FOREIGN PATENT DOCUMENTS

Examiner Initials	Foreign Patent Document		Country	Date of Publication (MM-DD-YYYY)	Translation	
	Number	Kind Code (if known)			Yes	No
				1		
				100	JUN	REC
				100	JUN	REC
				100	JUN	REC
				100	JUN	REC

## NON PATENT LITERATURE DOCUMENTS

Examiner Initials	Include name of author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.
RZ	"Electron Cyclotron Resonance Microwave Discharges for Etching and Thin-film Deposition," J. Vacuum Science and Technology A, Vol. 7, pp. 883-893 (1989) by J. ASMUSSEN;
RZ	"Low-temperature Deposition of Silicon Dioxide Films from Electron Cyclotron Resonant Microwave Plasmas," J. Applied Physics, Vol. 65, pp. 2457-2463 (1989) by T.V. HERAK et al.;
RZ	"New Approach to Low Temperature Deposition of High-quality Thin Films by Electron Cyclotron Resonance Microwave Plasmas," J. Vac. Sci. Tech. B, Vol. 10, pp. 2170-2178 (1992) by T.T. CHAU et al.;

Examiner Signature	Rudy Jennings	Date Considered	August 27, 2002
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EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant. SEND TO: Assistant Commissioner for Patents, Washington, D.C. 20231.

